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12-19-03

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Horne L. KOH

Serial No. 09/928,473

Filed: August 14, 2001



: Group Art Unit: 2812

: Examiner:

For: TOOL SERVICES LAYER FOR PROVIDING TOOL SERVICE FUNCTIONS
CONJUNCTION WITH TOOL FUNCTIONS

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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

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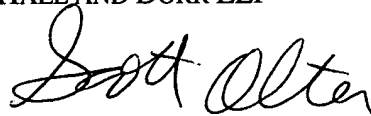
Serial No. 09/928,476

to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

HALE AND DORR LLP

A handwritten signature in black ink, appearing to read "Scott Alter", written over the printed name.

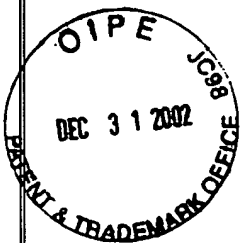
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INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(PTO-1449)



ATTY. DOCKET NO.
005123
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APPLICANT
Horne L. KOH

FILING DATE
August 14, 2001

GROUP
2812

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PUBLICATION / PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
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	5,375,064	12/20/94	Bollinger			12/02/93
	5,599,423	02/04/97	Parker et al.			06/30/95
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	WO 95/34866	12/21/95	WO			
	WO 98/45090	10/15/98	WO			
	EP 0 881 040 A2	12/02/98	Europe			
	WO 99/25520	05/27/99	WO			
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	EP 1 092 505 A2	04/18/01	Europe			


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	Hu, Albert, Kevin Nguyen, Steve Wong, Xihua Zhang, Emanuel Sachs, and Peter Renteln. 1993. "Concurrent Deployment of Run by Run Controller Using SCC Framework." IEEE/SEMI International Semiconductor Manufacturing Science Symposium. pp. 126-132.
	Hu, Albert, He Du, Steve Wong, Peter Renteln, and Emanuel Sachs. 1994. "Application of Run by Run Controller to the Chemical-Mechanical Planarization Process." IEEE/CPMT International Electronics Manufacturing Technology Symposium. pp. 371-378.
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	Suzuki, Junichi and Yoshikazu Yamamoto. 1998. "Toward the Interoperable Software Design Models: Quartet of UML, XML, DOM and CORBA." Proceedings IEEE International Software Engineering Standards Symposium. pp. 1-10.
	Klein, Bruce. June 1999. "Application Development: XML Makes Object Models More Useful." Informationweek. pp. 1A-6A.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

INFORMATION DISCLOSURE CITATION IN AN APPLICATION 			ATTY. DOCKET NO. 005123 USA/Consilium/Consilium		SERIAL NO. 09/928473 RECEIVED JAN - 2 2003 TECHNOLOGY CENTER 2800	
			APPLICANT Horne L. KOH			
			FILING DATE August 14, 2001		GROUP 2812	
U.S. PATENT DOCUMENTS						
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	WO 01/52055 A3	07/19/01	WO			X
	WO 01/57823 A2	08/09/01	WO			X
	EP 1 182 526 A2	02/27/02	Europe			X
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	Chemali, Chadi El, James Moyne, Kareemullah Khan, Rock Nadeau, Paul Smith, John Colt, Jonathan Chapple-Sokol, and Tarun Parikh. July/August 2000. "Multizone Uniformity Control of a Chemical Mechanical Polishing Process Utilizing a Pre- and Postmeasurement Strategy." J. Vac. Sci. Technol. A, Vol. 18(4). pp. 1287-1296. American Vacuum Society.					
	Jensen, Alan, Peter Renteln, Stephen Jew, Chris Raeder, and Patrick Cheung. June 2001. "Empirical-Based Modeling for Control of CMP Removal Uniformity." Solid State Technology, Vol. 44, No. 6, pp. 101-102, 104, 106. Cowan Publ. Corp.: Washington, D.C.					
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	November 12, 2002. International Search Report from PCT/US02/19063.					
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